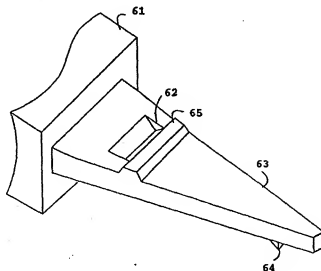




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(54) Title: CANTILEVER WITH INTEGRATED DEFLECTION SENSOR



(57) Abstract

A cantilever for scanning probe microscopy and other force of deflection measurements is described; said cantilever comprising at least one integrated strain sensing element within a constriction section (62). The cantilever is improved over known cantilevers by reducing the longitudinal extension of the constriction, such that its contribution to the total deflection of the cantilever is reduced. The design of the cantilever is further improved by applying a beam (63) with an essentially triangular cross section in either a vertical or a horizontal plane or both.

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DESCRIPTION

Cantilever with integrated deflection sensor

This invention relates to a cantilever beam, in particular for a scanning probe apparatus, which beam includes strain sensor elements for converting its mechanical movements or displacements into electrical signals, with said signals being for example characteristic of the structure of the scanned surface.

BACKGROUND OF THE INVENTION

Cantilevers of the kind to which the present invention is directed are for example described in the US Patent US-A-5345815. In the described microminiature cantilever structure a piezoresistive resistor is embedded in at least the fixed end of the cantilever arm. Deflection of the free end of the cantilever arm produces stress along the cantilever. That stress changes the piezoresistive resistor's resistance at the base of the cantilever in proportion to the cantilever arm's deflection. Resistance measuring apparatus is coupled to the piezoresistive resistor to measure its resistance and to generate a signal corresponding to the cantilever arm's deflection.

The microminiature cantilever is formed on a semiconductor substrate. A portion of the free end of the cantilever arm is doped to form an electrically separate U-shaped piezoresistive resistor. The U-shaped resistor has two legs oriented parallel to an axis of the semiconductor substrate having a non-zero piezoresistive coefficient. A metal layer is deposited over the semiconductor's surface and patterned to form an electrical connection between the piezoresistive resistor and a resistance measuring circuit, enabling measurement of the piezoresistive resistor's resistance. Finally, the semiconductor substrate below the cantilever arm is substantially

- 1 removed so as to form a suspended cantilever structure. For the use of the
cantilever in scanning probe microscopy and related applications, a tip is
mounted on the free end of the cantilever.
- 5 While the type of cantilever described in US-A-5 345 815 is closely related
to the kind to which the present invention is directed, there are numerous
examples of miniature accelerometers and pressure gauges are known to
the art which bear some resemblance to a cantilever structure. A careful
analysis of these structures however reveals that they are not applicable in
10 SPM due to an insufficient flexibility of the suspended arm, which is either
formed as or carries a stiff mass. An example of such an accelerometer is
described by L.M. Roylance and J.B. Angell in: IEEE Transactions on
Electron Devices, Vol. ED-26, No. 12, Dec. 79 pp. 1911 - 1917.
- 15 independent from the specific cantilever structure and its application,
attempts are known to improve the sensitivity of the piezoresistive strain
measurement by design optimization. Calculations and experiments
published for example in: Sensors and Actuators 17 (1989), pp. 225-233, lead
to an linearly and exponentially tapered resistor layer on the cantilever.
- 20 Another proposal for an optimized design is described in US-A-4 605 919,
where the cantilever has a groove at its base end. The piezoresistive sensor
bridges the groove. Though superior sensitivity of this design over others is
claimed, the proposed design is found to be difficult to realize, in particular
when the thickness of the cantilever is less than 10 μm .
- 25 It is therefore an object of the current invention to improve the design of the
known cantilever such as to increase the sensitivity and the signal-to-noise
(S/N) ratio of the deflection measurement.

SUMMARY OF THE INVENTION

The invention is characterized by the features as set forth in the appended claims.

The cantilever of the invention is particularly characterized by having a constriction section of reduced lateral dimensions and/or Young's modulus. The lateral dimension can be thickness and width in case of a beam-type cantilever structure with rectangular cross section or the diameter in case of a cylindrical cantilever. The Young's modulus defines the elasticity of a material. It can be locally altered by replacing part of the base material with another material or by changing the elasticity of the material using chemical or physical processes, such as doping, ion implanting, or high-energy radiation.

Another important feature of the cantilever in accordance with the invention is that an integrated strain sensor, which detects the deflection of the cantilever, is fully in contact with or embedded in the cantilever even at the site of the constriction. This is seen as a major advantage over the bridge-type strain sensors as proposed for example in US-A-4 605 919 for the reason of being easier to implement without suffering a significant loss in sensitivity. A bridge-type sensor would in addition considerably reduce the effect of the constriction when the total thickness of the cantilever is less than 10 μm .

Yet another important feature of the invention is that the length of this constriction section is significantly smaller than the total length of the cantilever. While the ratio of both lengths should be at least 1:5 to give satisfactory results, more preferably 1:10 or even 1:100, no corresponding upper limit can be given as the amplification increases with a decreasing length of the constriction. When utilizing for example an artificially induced hairline crack as a constriction, ratios of 1:10000 and even 1:100000 seem achievable.

1 The cantilever in accordance with the present invention may alternatively be
characterized by referring to the known electro-mechanical transducers with
a hinge section as commonly encountered in the field of miniaturized
pressure sensor and accelerometers: These devices are not suitable for the
5 kind of application to which the current invention is related. The known
pressure sensors and accelerometer, as for example described in the IEEE
Transactions on Electron Devices, Vol. ED-26, No. 12, Dec. 79 pp. 1911 - 1917
by L.M. Roylance and J.B. Angell or In the US Patent No. 4 605 919 to
Wilner, usually have a rigid mass or paddle attached to the soft hinge
10 section. It is due to the relatively small stiffness of the hinge section and the
rigidity and large mass of the foremost part of the transducer, that these
known devices are not applied in the field of scanning probe microscopy.

Hence contrary to these known transducers, It is a further characteristic
15 feature of the invention that the ratio of the compliance, i.e. the reciprocal of
the stiffness, C_c of a cantilever with a constriction to the compliance C_0 of
the cantilever without the constriction $C_c/C_0 = 1 + n\lambda/\varepsilon$ is less than 10, more
preferably a value close to 3, however not less than 0.1. The factor n is
determined by the shape of the cantilever: for a rectangular beam, the
20 value of n equals 3; for a triangular-shaped beam n reduces to 2. The letter
 λ denotes a longitudinal constriction factor defined as the ratio of the
effective length of the constriction over the remaining length of the
cantilever; and ε is defined as a transversal constriction factor by the
product of the third power of the ratio of the thicknesses, the ratio of the
25 widths, and the ratio of the Young's moduli of the cantilever in the
constriction section and in the remaining part of the cantilever, respectively.
The factor ε hence characterizes the lateral dimensions and the material
properties of the constriction.

30 This ratio $n\lambda/\varepsilon$ can be estimated for a typical accelerometer like the one
described by Roylance and Angell (see above) to be at around

$$n \times \frac{\lambda}{c} \approx 2 \times \frac{\frac{0.4\text{mm}}{1.2\text{mm}}}{\left(\frac{40\mu\text{m}}{200\mu\text{m}}\right)^3 \times \left(\frac{0.2\text{mm}}{1\text{mm}}\right) \times 1} = 375.$$

The characteristic feature of the cantilever and its constriction section as proposed above ensures that the whole cantilever remains flexible and is not reduced to a stiff mass attached to a soft hinge. This flexibility, not encountered among the known accelerometers and pressure gauges, is necessary in SPM related applications to achieve the sensitivity required in a large bandwidth.

Apart from reducing the length of the constriction section of the cantilever structure, it is also a preferred feature of the invention to reduce the longitudinal dimensions of the active area of the deflection sensing elements which are integrated in the constriction section. For V-shaped grooves, the sensing elements therefore are preferably designed such as extending along the groove.

As the employed deflection sensors are sensitive to the physical stress built up when the cantilever is bend, several preferred embodiments of the invention are characterized by optimizing the stress distribution within the cantilever structure. Thus the sensitivity of the deflection sensors in the constriction area can be enhanced by shaping the cantilever triangularly in the longitudinal direction, e.g., by tapering it towards the foremost end, by using a triangular cross section, or by a combination of both methods.

In a further preferred embodiment of the invention, the cantilever has a section of enhanced stiffness in the immediate vicinity of the constriction section. This length of this further section does not extend over the total length of the cantilever; it is preferably restricted to less than 0.5 times the total length of the cantilever. Even more preferred it has approximately the length as the constriction section, i.e. both lengths differ by 30 per cent at

- 1 the most. In a preferred embodiment, the section with enhanced stiffness is realized by enlarging the cross section of the cantilever. Other possibilities include increasing the Young's module of the cantilever in this section.
- 5 As mentioned above a constriction in accordance with the present invention is not restricted to a change of lateral dimensions. It can also be achieved by altering the elastic constants of the material in the constriction section by replacing part of the base material of the cantilever by a more elastic materials, e.g. an organic polymer. It may be instructive to regard the
- 10 lateral, i.e., the geometric constrictions as an extreme example of such an elastic constriction wherein the base material is replaced by air.

- Possible usage of the new cantilever is not restricted to Scanning Probe Microscopy (SPM) related applications. As the new type of cantilever
- 15 enhances the sensitivity for any deflection measurement, it can be employed in various types of micromechanical forcemeters, e.g. accelerometers or pressure gauges.

- These and other novel features believed characteristic of the invention are set forth in the appended claims. The invention itself however, as well as a preferred mode of use, and further objects and advantageous thereof, will best be understood by reference to the following detailed description of illustrative embodiments when read in conjunction with the accompanying drawings.
- 20
- 25

30

DESCRIPTION OF THE DRAWINGS

The invention is described in detail below with reference to the following drawings:

FIGs. 1A, B show different views on a first type of constriction section (thickness constriction) in a cantilever in accordance with the present invention.

FIGs. 2A, B show different views on a second type of constriction section (width constriction) in a cantilever in accordance with the present invention.

FIGs. 3A, B show different views on a third type of constriction section (symmetric thickness constriction) in a cantilever in accordance with the present invention.

FIGs. 4A - 4C illustrate different positions for a strain sensing element.

FIGs. 5A, B show different views on a cantilever with a constriction section and a section of enhanced stiffness.

FIG. 6 shows a tilted top view on a triangular cantilever in accordance with the present invention.

MODE(S) FOR CARRYING OUT THE INVENTION

Referring to Fig. 1, some basic parameters are introduced and defined for a better understanding and appreciation of the present invention. Figures 1 A, B show a tilted top view and a cross section, respectively, of a cantilever beam with a constriction. The whole cantilever structure consists of three parts: a supporting structure 11, which is assumed for the following to be

1 fixed; a constriction section 12; and, attached to it, the cantilever beam 13
 itself, with a tip (not shown). The transitional part of the cantilever between
 the support structure 11 and the constriction section is held short for
 rectangular shaped cantilevers, as in these types of cantilevers the strain
 5 decreases linearly with the distance from the clamped or supported end.
 For triangular cantilevers (cf. Fig. 6), where the strain is constant along the
 length of the whole beam, the constriction section may be placed at a larger
 distance from the supported end.

10 The characteristic dimensions, i.e., length L, width W, and thickness T of the
 cantilever constriction section 12 will be labeled in the following description
 by a subscript "1"; those of the cantilever beam by a subscript "2."

The deflection of the cantilever is considered to be in direction of the
 15 thickness T as indicated by the arrow in Fig. 1B. Under these conditions,
 the strain amplification and the stiffness reduction caused by the
 constriction is dominated by the "transverse constriction factor" ϵ , which in
 turn is defined as

$$20 \quad \epsilon \equiv \frac{E_1}{E_2} \frac{T_1^3}{T_2^3} \frac{W_1}{W_2} \equiv \eta \tau^3 \beta; \quad [1]$$

and the "longitudinal factor" defined by

$$25 \quad \lambda \equiv \frac{L_1}{L_2}, \quad [2]$$

30 wherein L_1 is the effective length of the constriction, which is larger than the
 geometrical length but usually does not exceed this length by more than a
 factor of two; and $L_1 + L_2 = L_c$ is the total length of the cantilever.

- 1 Using basic relations of strain calculation in a suspended beam, the strain σ_e at the top or bottom side of the constriction placed at the clamped end of the beam compares to the strain σ_u of a beam with a uniformly rectangular cross section, equal stiffness, and dimensions
- 5 $L_u = L_e$, $T_u = T_e$ but $W_u E_u < W_e E_e$ according to :

$$v \equiv \frac{\sigma_e}{\sigma_u} = \tau / \left(1 - \frac{1-\varepsilon}{(1+\lambda)^n} \right) \simeq \tau / (n\lambda + \varepsilon), \quad [3]$$

10

wherein $n = 3$ for a rectangular beam (Fig. 1A) and $n = 2$ for a triangular beam (FIG. 6).

- Equation [3] shows that both, ε and λ , i.e., the transverse and the longitudinal constriction factor, respectively, affect the strain enhancement.
- 15 Although the thickness ratio τ contributes with the third power to ε , it enters the strain amplification linearly as the prefactor in eqn. [3]. The optimum value of τ

20

$$\tau_{opt} = ((1+\lambda)^n - 1) / (2\beta\eta)^{1/3} \simeq (n\lambda / 2\beta\eta)^{1/3} \quad [4]$$

maximizes the strain amplification for given λ , β , and η at

25

$$v_{max} = \frac{2}{3} (1+\lambda)^n (2\beta\eta ((1+\lambda)^n - 1)^2)^{-1/3} \simeq \frac{2}{3} (2(n\lambda)^2 \beta\eta)^{-1/3}. \quad [5]$$

The corresponding optimal transverse constriction factor ε then is

30

$$\varepsilon_{opt} = \frac{n\lambda}{2}. \quad [6]$$

1 The width factor β and the elasticity factor η of the transverse constriction factor increase the highest amplification attainable by a thickness
 5 constriction alone by a factor of $(\beta \eta)^{-1/2}$. Taking for example a cantilever with $L_c = 0.1$ mm, $W_2 = 20$ μ m, $T_2 = 2$ μ m, and $\lambda = 0.01$, $\eta = 1$, and assuming a thickness constriction alone ($\beta = 1$), equations [4], [6], and [5]
 result in $\tau_{opt} = 0.247$, ($\epsilon_{opt} = 0.015$) and $v_{max} = 5.2$, respectively. With an additional width constriction ($\beta = 0.1$), however, the corresponding results
 are $\tau_{opt} = 0.53$, ($\epsilon_{opt} = 0.015$) and $v_{max} = 11.5$. The thickness constriction τ
 is therefore primarily used to optimize ϵ (eqn. [6]), taking into account that
 10 it is difficult to make β approximately equal to λ in a cantilever with a typical width of 20 μ m or below. It should be noted that in the case of
 $\beta \eta < \frac{1}{2} n \lambda = \epsilon_{opt}$, a maximal strain amplification is achieved with $\tau_{opt} > 1$,
 i.e., even by enlarging the thickness within the constriction section. Therefore it is seen as the most prominent feature when designing a
 15 constriction in accordance with the present invention to approach the optimal value of ϵ as given by equation [6], independently from the actual layout of the secondary constrictions features τ , β , and η .

While the preceding sections basic relations are described considered as
 20 being helpful to fully appreciate the achievements of the present invention, in the following different embodiments of the invention are presented. The respective embodiments illustrate various types of constrictions. However, they do not present all variants and modification apparent to a skilled person.

25 All of following embodiments are manufactured using an ion milling technique. In this technique, the pre-fabricated cantilever is enclosed in a vacuum chamber at a base pressure of about 2.3×10^{-6} mbar. From an ion source, gallium (Ga) ions are accelerated to by a high voltage (10 - 30 kV).
 30 and focussed on the target. A current of 12 - 300 pA is used to erode the material at the target spot. The efficiency of the process can be enhanced by directing a stream of chloride molecules to a target area. Grooves, trenches, holes, and other constrictions can be comfortably produced by

1 applying this method. The equipment for ion milling is commercially available.

Other methods exist and are partly used, as described for example in K. Pedersen, "Silicon as a Mechanical Material" in: Proceedings of the IEEE, 5 Vol. 70, No. 5, May 1982, pp. 421 - 457; as well as in US-A-5 345 815, which are more suitable for mass production. Undercut structures, such as applied to manufacture the pre-fabricated cantilevers, can be etched exploiting the anisotropic effects of etching silicon with etchants like KOH 10 and EDP. These etchants provide a highly anisotropic etch rate for the (100) and (111) oriented surfaces of silicon. Structures which should be preserved in the etching process are protected by masking layers, by doping, or by the appropriate choice of etching parameters, such as etching time, orientation of the surface, and etchant. Piezoresistive zones are 15 generated and patterned by using for example arsenic implanted through a window of a protection layer. Electrical conductive paths are provided by sputtering of a metal. All of these manufacturing steps are well known, and hence are not regarded as being primary features of the current invention.

20 Referring now to FIGs. 2 A, B, a constriction is achieved by a vertical hole 22 in the cantilever beam. Though an extreme amount of material is taken from the constriction section, both remaining bridges 221, 222 of base material provide a sufficient resistance against unwanted lateral deflection.

25 Another type of constriction is illustrated with reference to Figs. 3A, B. The constriction section 32 consists of two prismatic grooves etched into the faces of the cantilever. Bridges between the rest of the cantilever beam 33 and the support section 31 are left at both sides and between the grooves. The design is characterized by leaving a large cross section for heat 30 transport and a bridge for electrical leads along the cantilever. The strain enhancing properties of the constriction section are however maintained as most of the bridge material is close to the line of zero strain, also known as neutral line 34.

1 The variants of figure 4 show the strain sensor mounted at different
locations within the constriction section. In the embodiment of Fig. 4A, the
sensor 451 is buried at the bottom of the groove 421; in the embodiment of
Fig. 4B it is placed opposite to the groove 422. In the embodiment of Fig.
5 4C, the strain sensor 453 is positioned at both (longitudinal) rims of the
prismatic groove 423, which defines the constriction section.

In Figs. 5A, B, the constriction 52 is followed by a section 55 having an
enlarged cross section. This section provides an area of enhanced stiffness
10 at the transition from the constriction to the remaining cantilever 53. This
area may also extend into the constriction section 52 itself, e.g., by
increasing the thickness of the two bridges 521, 522.

Independent from the type of constriction, the strain enhancement can be
15 improved by the shaping the remaining cantilever beam itself. It is found
that, when replacing its usual rectangular cross section by a triangular one,
the sensitivity of the strain measurement can be further improved. A
triangularly shaped cantilever beam has the particular advantage of
showing a uniform strain in longitudinal direction, hence providing the
20 possibility of placing the constriction section at a larger distance from the
clamped end. In Fig. 6, the cantilever 63 has a triangular cross section in a
horizontal plane. The cantilever further has a constriction formed by
prismatic grooves 62 in its shown and hidden face similar to those depicted
by figures 3A and 3B. The cantilever also shows an area of enlarged cross
25 section 65, which reduces the effective length of the constriction (cf. Fig. 5).
A tip 64 is attached to the foremost part of the cantilever for use in a AFM
type application, e.g. surface inspection and/or modification. It should be
noted that this and all other figures are not drawn to scale.

30 It is further noteworthy that the cantilever with a constriction can be used to
enhance the sensitivity of known micromechanical pressure gauges or
accelerometers. These instruments usually comprise a suspended stiff mass
or a diaphragm supported by one or a plurality of beams, into which in most

1 cases strain sensors are embedded. By introducing constrictions sections
as described herein into those support beams, any deflection of the
suspended mass or diaphragm can be traced with increased precision.
The teaching of the present invention can thus be transferred to and used in
5 a large variety of micromechanical devices which require some sort of
deflection measurement.

As the above described manufacturing process can and, with respect to the
anisotropic etching, are applicable to batch or mass manufacturing, the
10 present invention can be readily extended to arrays of equal of slightly
modified cantilevers. These arrays could be used in a variety of
applications, such as storage devices, touch sensitive screens, and the like.

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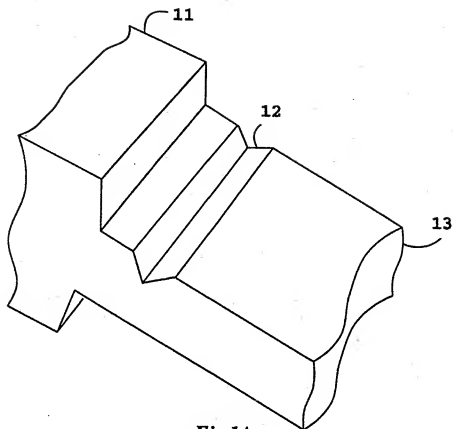
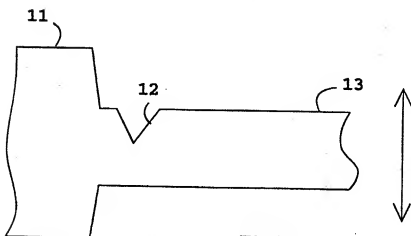
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CLAIMS

- 1
1. Cantilever having a constriction section (12; 62) of reduced lateral dimensions and/or reduced Young's modulus and at least one integrated strain sensing element (451; 452; 453) forming a layer fully in contact with and/or embedded in said cantilever, wherein the length (L_1) of the constriction is less than 1/5 of the total length of the cantilever and the ratio $n\lambda/\epsilon$ is less than 9, with:
- 5
- 10 n being a geometrical factor in the range of 1-10 depending on the shape of the cantilever;
- 15 λ being a longitudinal constriction factor defined as the ratio of the length L_1 over the remaining length of the constriction; and
- 20 ϵ being a transversal constriction factor defined as a product of the third power of the ratio of the thicknesses, the ratio of the widths, and the ratio of the Young's moduli of the cantilever in the constriction section and in the remaining part of the cantilever, respectively.
- 25
2. The cantilever of claim 1, comprising an attached tip (64) for probing the surface of a sample.
3. The cantilever of claim 1, wherein the constriction section essentially consists of at least one groove (12; 32; 62) extending in lateral direction.
4. The cantilever of claim 1, having in the immediate vicinity of the constriction section a section (55; 65) with an enhanced stiffness.
- 30 5. The cantilever of claim 1, having in the immediate vicinity of the constriction section a section (55; 65) with an enlarged cross section.

- 1 6. The cantilever of claim 1, wherein the sensing element (451: 452)
essentially extends in a lateral direction with respect to the beam
section.
- 5 7. The cantilever of claim 1, wherein the beam section (63) has an
essentially triangular cross section in either a horizontal plane, or in a
vertical plane or in a horizontal and vertical plane.
8. Data storage system, comprising at least one cantilever in accordance
10 with claim 1.
9. An array comprising a plurality of cantilevers in accordance with claim
1.
- 15
- 20
- 25
- 30

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**Fig. 1A****Fig. 1B**

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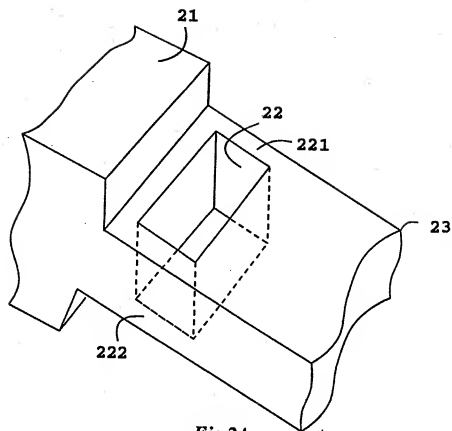


Fig. 2A

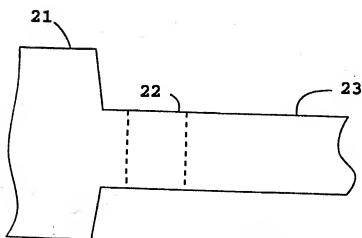
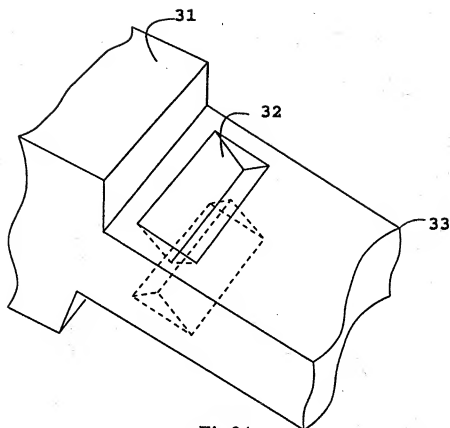
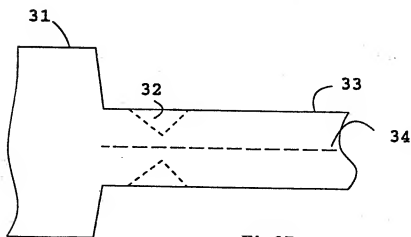
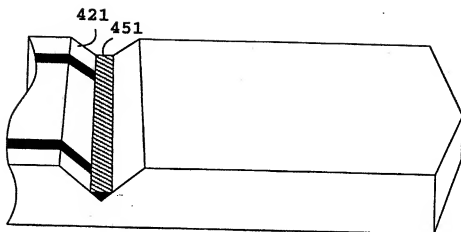
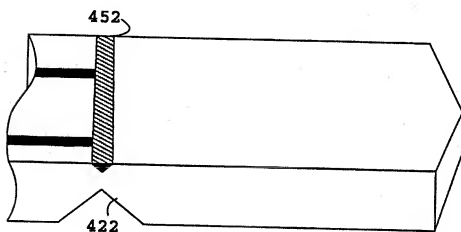
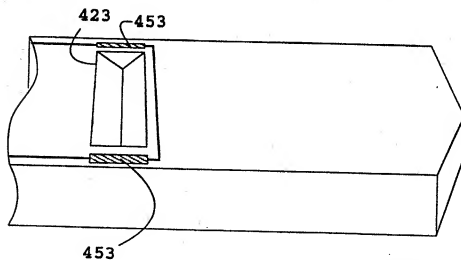


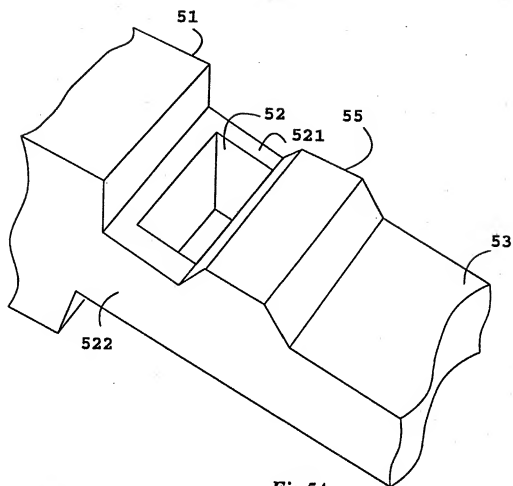
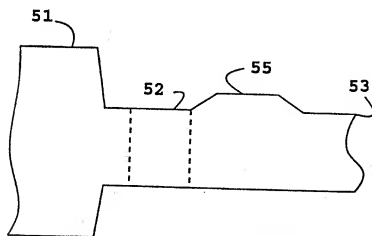
Fig. 2B

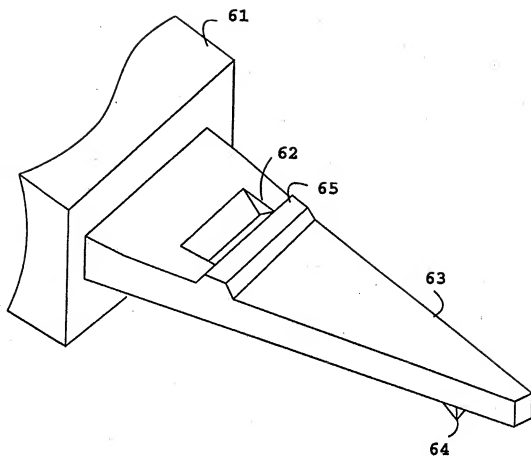
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**Fig.3A****Fig.3B**

*Fig. 4A**Fig. 4B**Fig. 4C*

5/6

*Fig. 5A**Fig. 5B*

*Fig.6*